

Semiconductor Process Gases

All mixtures are Certified Master Class™.

Arsine AsH₃

Typically used for silicon semiconductor doping applications and photovoltaic film deposition where the N-type dopant property provided by arsine is desired.

Concentration*	Size	Contents		Balance Gas			
		CF	m ³	Argon	Helium	Hydrogen	Nitrogen
5 – 100 ppm	30AL	140	4	•			
		130	4				•
		125	4		•		
		120	3			•	
	7AL	28	0.8	•			
		26	0.7				•
		25	0.7		•		
		24	0.7			•	
101 ppm – 50%	44P	201	6	•			
		190	5				•
		180	5		•	•	

* Concentrations >10% may be at reduced pressure and contents.

Please note: Shelf life is 1 year.